



Patent
Attorney's Docket No. 027260-295

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

Filed: May 26, 1999

For: PHOTOMASK, FABRICATION
METHOD OF PHOTOMASK, AND
FABRICATION METHOD OF
SEMICONDUCTOR INTEGRATED
CIRCUIT

Group Art Unit: 1756

Examiner: S. Mohamedulla

PRELIMINARY AMENDMENT/STATEMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Date: April 4, 2001

Sir:

This preliminary amendment is filed in order to facilitate processing in the above-identified application and is filed in response to the Advisory Action dated March 14, 2001 (Paper No. 8).

REMARKS

This preliminary amendment is filed in order to respond to note no. 6 in the Advisory Action dated March 14, 2001. In particular, Applicant respectfully traverse the Examiner's statement "while *Hur* and *Lee* do not specifically teach chemical-mechanical polishing the phase shift film, it is an obvious variation of *Hur* or *Lee* to polish it as the references teach performing chemical-mechanical polishing on other areas of the mask. Applicant argues that *Hur* and *Lee* do not teach a reflection preventing film, however, they teach a light shading film". Applicant respectfully point out that a reflection preventing